

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

#4
PRE
Amend
A
7/19/00

In re the application of:

Tatsui Enami, *et al.*

Serial No.: NEW

Filed: March 3, 2000 (herewith)

For: ARF EXCIMER LASER DEVICE, SCANNING TYPE EXPOSURE DEVICE
AND ULTRAVIOLET LASER DEVICE

PRELIMINARY AMENDMENT

Honorable Commissioner
of Patents and Trademarks
Washington, D.C. 20231

March 3, 2000

Dear Sir:

Prior to an examination on the merits, please amend the above-identified application as set forth below:

IN THE CLAIMS:

Claim 3, lines 6 and 7, "or 2".

Please add the following new claim:

a¹ --7. A scanning type exposure device which performs exposure of an entire semiconductor chip on a wafer by moving the wafer while irradiating a pulsed laser light to each of a plurality of irradiating regions smaller than an area of the semiconductor chip, wherein a light source for oscillating the laser light is the ArF excimer laser according to claim 2.--